

July 21, 2025

The Honorable Bruce Westerman  
Chairman  
House Committee on Natural Resources  
1324 Longworth House Office Building  
Washington, D.C. 20515

Dear Chairman Westerman,

I am writing to express my appreciation for your leadership in streamlining and expediting the current federal environmental permitting and review process. Further streamlining in this area will facilitate timely investments in critical sectors, such as semiconductor manufacturing, which are essential for bolstering America's dominance in artificial intelligence (AI), emerging technologies, and national and economic security.

As you know, Micron is building new large-scale semiconductor factories, or "fabs", that will manufacture the only leading-edge memory chips in the United States. The U.S. is on the cusp of a manufacturing renaissance due to breakthroughs in AI and other technologies large in part because of business and tax incentives recently passed by Congress and President Trump.

While the resurgence in manufacturing and AI leadership is crucial to America's national and economic security, the current burdensome regulatory environmental review process will continue to hinder rapid progress. Without immediate reform, American manufacturing will struggle significantly, ultimately prevent companies like Micron from meeting projected demand. The urgency for change cannot be overstated and it is imperative that policymakers and industry leaders come together to streamline these processes and enact the necessary reforms to secure our future.

We are particularly supportive of efforts to reduce permitting burdens related to the National Environmental Policy Act (NEPA), particularly where duplicative state and federal environmental reviews delay critical projects. Streamlining this process would accelerate the implementation of economic development investments, such as those by Micron, and would ensure every federal dollar is used efficiently and effectively. This approach would also maintain strong environmental protections by continuing to comply with other applicable regulations.

We are encouraged by promising bipartisan legislation such as *The Infrastructure Project Acceleration Act* led by Representatives Langworthy (R-NY) and Rep. Collins (R-GA). This bill would empower the lead federal agency to expedite NEPA reviews for qualifying projects while preserving state-level regulations, applying only in states with more stringent environmental standards than NEPA.

Additionally, we are encouraged by the Administration's reconsideration of the Particulate Matter National Ambient Air Quality Standards (PM 2.5). While there may be some evidence to support a reduction of the annual PM2.5 NAAQS, the new NAAQS of 9 µg/m<sup>3</sup> is not well supported, even within the scientific community, and creates challenges for expansion within the manufacturing sector. The PM

2.5 NAAQS should be reconsidered through review of the minority of Clean Air Scientific Advisory Committee (CASAC) positioning and/or a revision to the previous standard (12  $\mu\text{g}/\text{m}^3$ ) should be considered.

While this reconsideration is underway, permit applicants should be allowed to utilize the previous NAAQS to avoid unnecessary delays. Furthermore, critical industries that are imperative to U.S. national and economic security—such as advanced manufacturing, which includes semiconductor manufacturing—should receive an exemption from the rule. These sectors are foundational to America's technological leadership and must be protected from regulatory uncertainty that could hinder investment and innovation.

Please know that you have Micron's support in these efforts. We stand ready to assist in any way that may be helpful as you continue to champion reforms that enhance transparency, reduce unnecessary delays, and ensure that federal permitting serves the public interest effectively.

Thank you again for your leadership and dedication to this important issue.

Sincerely,

*Bo Machayo*

Bo Machayo

Head of U.S. Government & Public Affairs

**micron**